S/N 09/945,554 PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

SRAM CELLS WITH REPRESSED FLOATING GATE MEMORY, LOW

Applicant:

Leonard Forbes

Examiner:

Thomas L Dickey

Sekal No.:

09/945,554

Group Art Unit:

2826

Faled:

August 30, 2001

Docket:

1303.028US1

TUNNEL BARRIER INTERPOLY INSULATORS

## INFORMATION DISCLOSURE STATEMENT

MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 et. seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicant respectfully requests that this Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicant requests that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicant with the next official communication.

Pursuant to 37 C.F.R. §1.97(b), it is believed that no fee or statement is required with the Information Disclosure Statement. However, if an Office Action on the merits has been mailed, the Commissioner is hereby authorized to charge the required fees to Deposit Account No. 19-0743 in order to have this Information Disclosure Statement considered.

The Examiner is invited to contact the Applicant's Representative at the below-listed telephone number if there are any questions regarding this communication.

Respectfully submitted, LEONARD FORBES

By his Representatives,

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CERTIFICATE UNDER 37 CFR 1.8: The undersigned hereby certifies that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail, in an envelope addressed to: MS Amendment, Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this 34h day of August, 2004.

Amy Moriarty

Signature

PTO/S8/08A(10-01)
Approved for use through 10/12/02/. OMB 051-0019
US Patent & Trademerk Office: U.S. DEPARTMENT OF COMMERCE
or the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE 09/945,554 **Application Number** STATEMENT BY APP JOANT August 30, 2001 Filing Date (Use as many sheets as necessaly) Forbes, Leonard **First Named Inventor** SEP 0 1 2004 2826 **Group Art Unit** Dickey, Thomas **Examiner Name** Attorney Docket No: 1303.028US1 Sheet 1 of 1

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**DATE CONSIDERED EXAMINER**